

AMENDMENTS TO THE CLAIMS

1. (Currently Amended) An etch/strip apparatus integrated with cleaning equipment, comprising:

an etching line for etching and cleaning a substrate, said etching line comprising an etching module and a rinse module, for etching and rinsing a substrate prior to stripping, said etching module and said rinse module being unified such that a substrate is moved internally between said unified modules with no exposure to the outside thereof;

a stripping line for stripping the substrate, the stripping line being connected to the etching line;

a transfer module for moving the substrate from the etching line to the stripping line with no exposure of the substrate to air atmosphere;

a cleaning line installed on the stripping line to clean and dry the substrate; and

an elevator for conveying the substrate from the stripping line to the cleaning line.

2. (Cancelled)

3. (Cancelled)

4. (Previously Presented) The apparatus as claimed in claim 1, further comprising:

a loader for feeding the substrate to the etching line; and
an unloader for receiving the substrate from the cleaning line.

5. (Previously Presented) The apparatus as claimed in claim 4, wherein the etching line includes:

an etch module for etching the substrate from the loader; and
a rinse module for cleaning the substrate fed from the etch module.

6. (Currently Amended) An integrated etch/strip/clean apparatus, comprising:

an etching line for etching and cleaning a substrate;
a stripping line for stripping said substrate, said stripping line being unified with said etching line ~~such that the substrate stays inside of the unified lines during movement and processing, thereby reducing synchronization and hold times and an overall processing time through a transfer module, wherein said transfer module moves the substrate from said etching line to said stripping line while preventing the substrate from drying;~~

a cleaning line integrated with said etching and stripping lines to clean and dry the substrate; and

an elevator to transfer said substrate from said stripping line to said cleaning line.

7. (Original) The apparatus of claim 6, wherein said cleaning line is installed on said stripping line.

8. (Original) The apparatus of claim 6, wherein said etching line includes:
an etch module; and
a rinse module connected to said etch module.

9. (Cancelled)

10. (Currently Amended) The apparatus of claim 69, wherein said ~~transfer module includes~~ preventing the substrate from drying is accomplished by a pipe shower, ~~for~~ providing a fluid to prevent ~~on~~ the substrate ~~from~~ drying.

11. (Cancelled)

12. (Previously Presented) The apparatus of claim 6, further comprising:
a loader for loading the substrate to the etching line; and
an unloader for unloading the substrate from the cleaning line.

13. (Original) The apparatus of claim 12, wherein said loader includes at least one of a conveyor and a robot.

14. (Original) The apparatus of claim 12, wherein said unloader includes at least one of a conveyor and a robot.

15. (Previously Presented) The apparatus as claimed in claim 1, wherein the stripping line and the cleaning line are stacked to have a two-tier structure.--

16. (Previously Presented) The apparatus as claimed in claim 6, wherein the stripping line and the cleaning line are stacked to have a two-tier structure.